

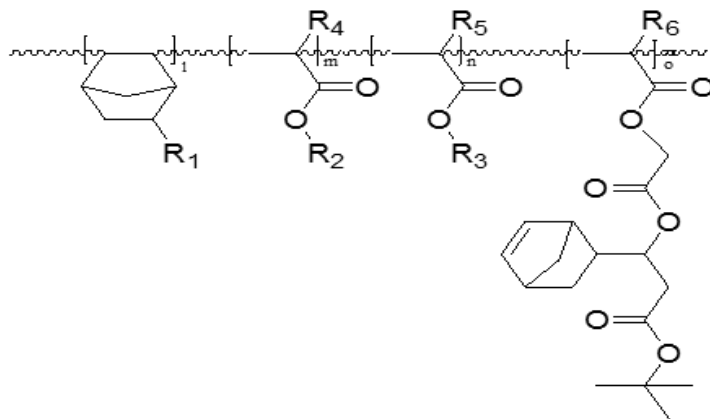
Abstract of the Disclosure

COPOLYMER FOR RESIST INCLUDING NOVEL ACRYL-BASED MONOMER AND RESIN COMPOSITION FOR RESIST INCLUDING THE SAME

5

A resist resin composition includes 100 parts by weight of a copolymer represented by Formula 3 below; 0.5 to 1.5 parts by weight of a photoacid generator and 700 to 1,500 parts by weight of a solvent:

<Formula 3>



10

wherein R₁, R₂, and R₃ are each independently a C₁₋₃₀ alkyl group or a C₃₋₃₀ cycloalkyl group that has or does not have hydrogen, an ether group, an ester group, a carbonyl group, an acetal group, an epoxy group, a nitrile group, or an aldehyde group, R₄, R₅, and R₆ are each independently hydrogen or a methyl group, and l, m, n, and o each independently refer to the number of repeating units in a main backbone and satisfy the conditions: l+m+n+o=1, 0≤l/(l+m+n+o)<0.4, 0<m/(l+m+n+o)<0.6, 0≤n/(l+m+n+o)<0.6, and 0<o/(l+m+n+o)<0.4.

15